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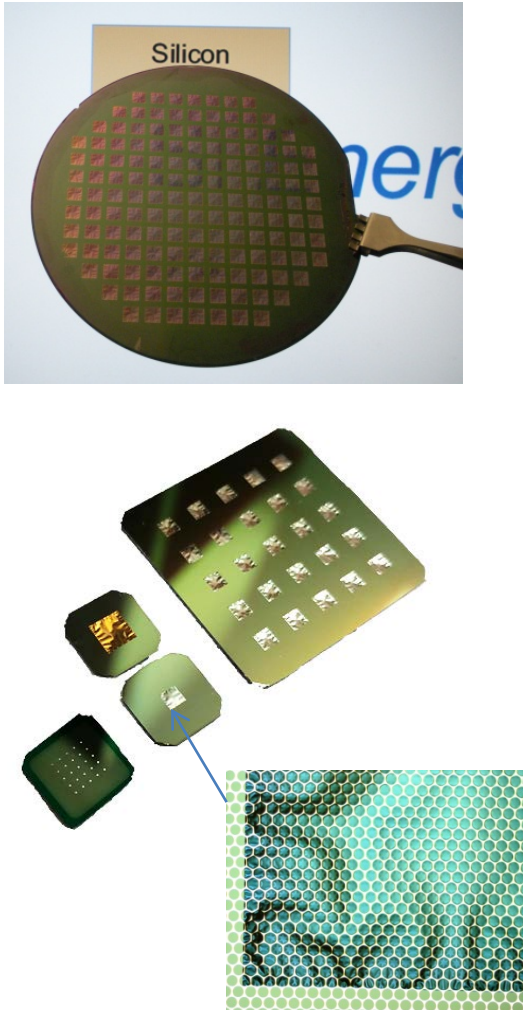
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Direct Hydrocarbon Fuel Cell – Battery Hybrid Electrochemical Device

Project PI: Masaru Tsuchiya

Co-PIs: Prof Shriram Ramanathan and Prof Cynthia Friend

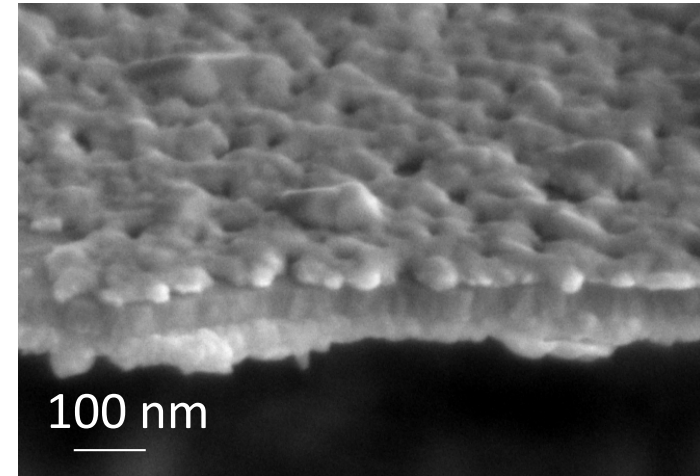
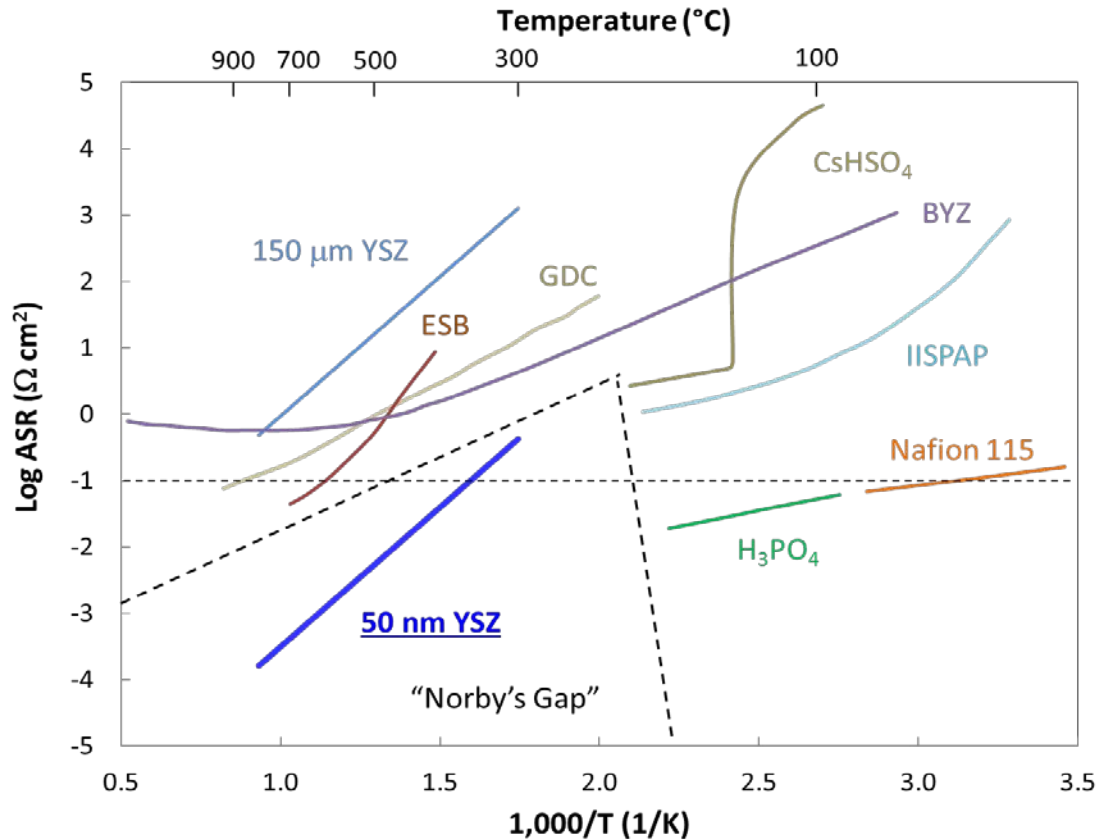
About SiEnergy Systems



- SiEnergy was formed in 2007 by Allied Minds (LSE: ALM), an innovative U.S. science and technology development and commercialization company.
- The technology was originally based on the research of Professor Ramanathan of Harvard University.
- In the period from 2007 to 2010, SiEnergy worked through an SRA with Harvard.
- Scalability of core technology (ultra-thin film SOFC) was demonstrated in 2010.
- SiEnergy moved to its own facility in Cambridge in 2011, and expanded R&D team in 2012.
- ARPA-E REBELS program to develop dual-mode device started in 2014.

Ultra-thin film SOFC

Platform to demonstrate fuel cell at 300-500 °C

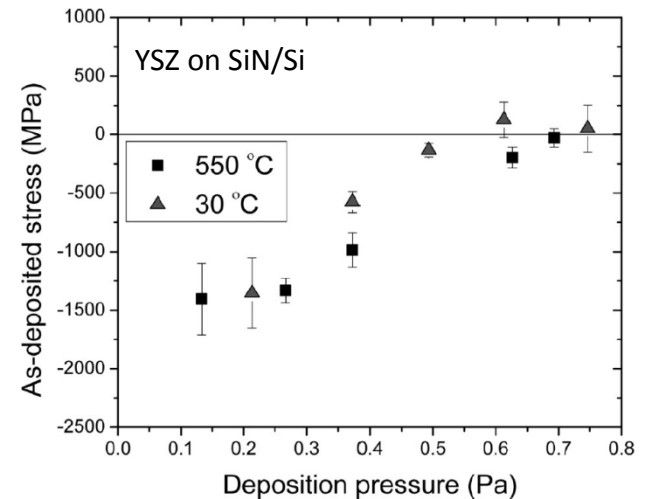
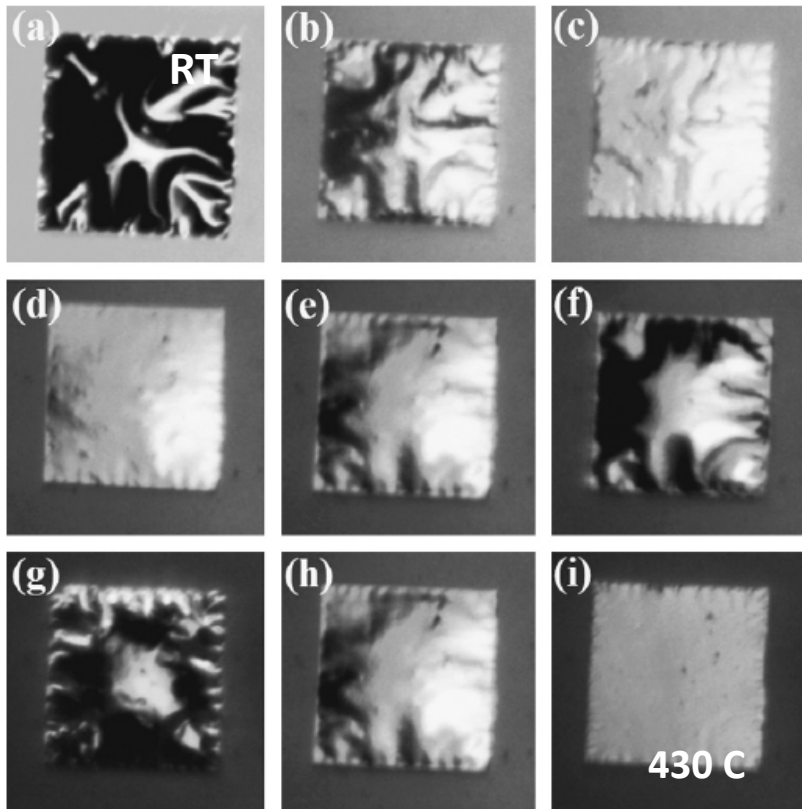


M. Tsuchiya *et al.*,
Nature Nanotechnology, 6, 282 (2011).

- Area specific resistance (ASR) of 50 nm YSZ is only $0.005 \Omega \text{ cm}^2$ at 500 °C.
- Thin film YSZ is often required for new electrolyte materials as blocking layer.
→ *Nanoscale YSZ provides the lowest practically achievable resistance for 300-500 °C.*

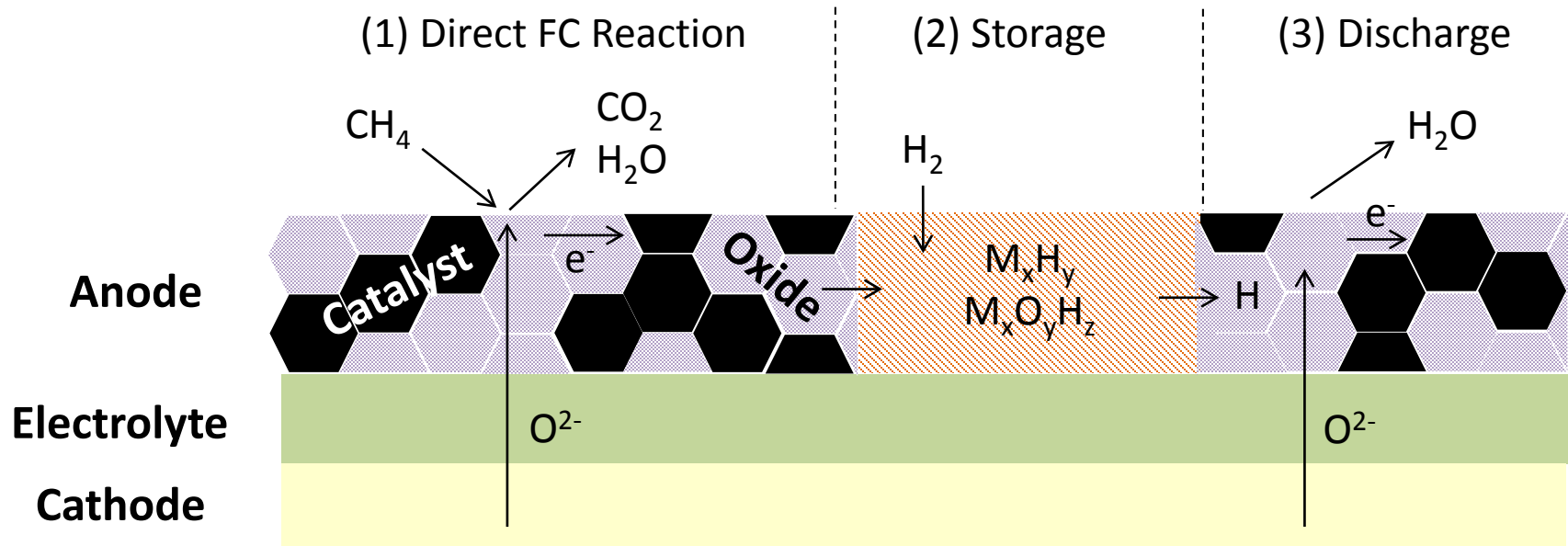
Key advantage of thin-film deposition for SOFC fabrication

Ease of integration of dissimilar materials
(i.e., flexible materials selection)



- Initial stress can be tuned by process conditions to counter-balance thermal stress applied during heating/cooling.

Technology Overview



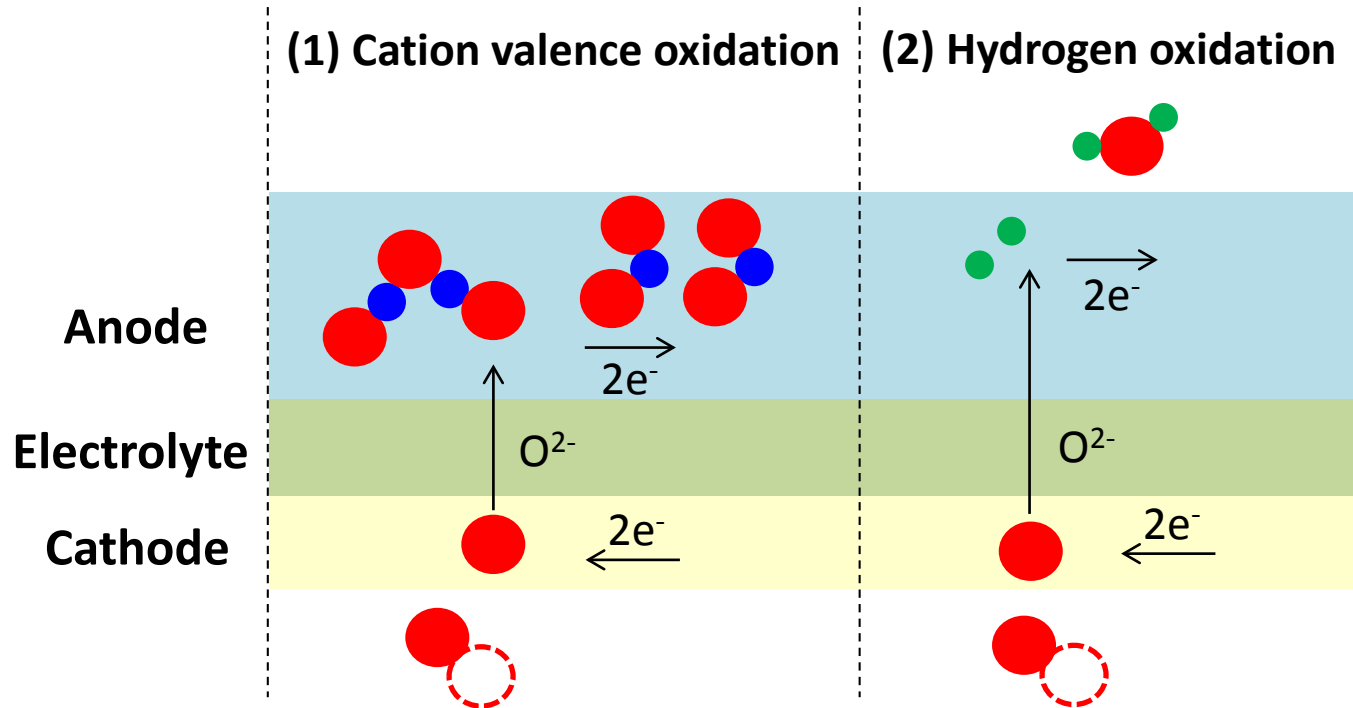
Key novelties of the proposed project

- ***In-situ* charge storage in anode to enable battery-like transient response**
 - Transition metal oxide and/or metal hydride to store hydrogen
- **Direct hydrocarbon operation to avoid the use of fuel processing units**
 - Carbide catalyst to activate C-H bond at low temperature



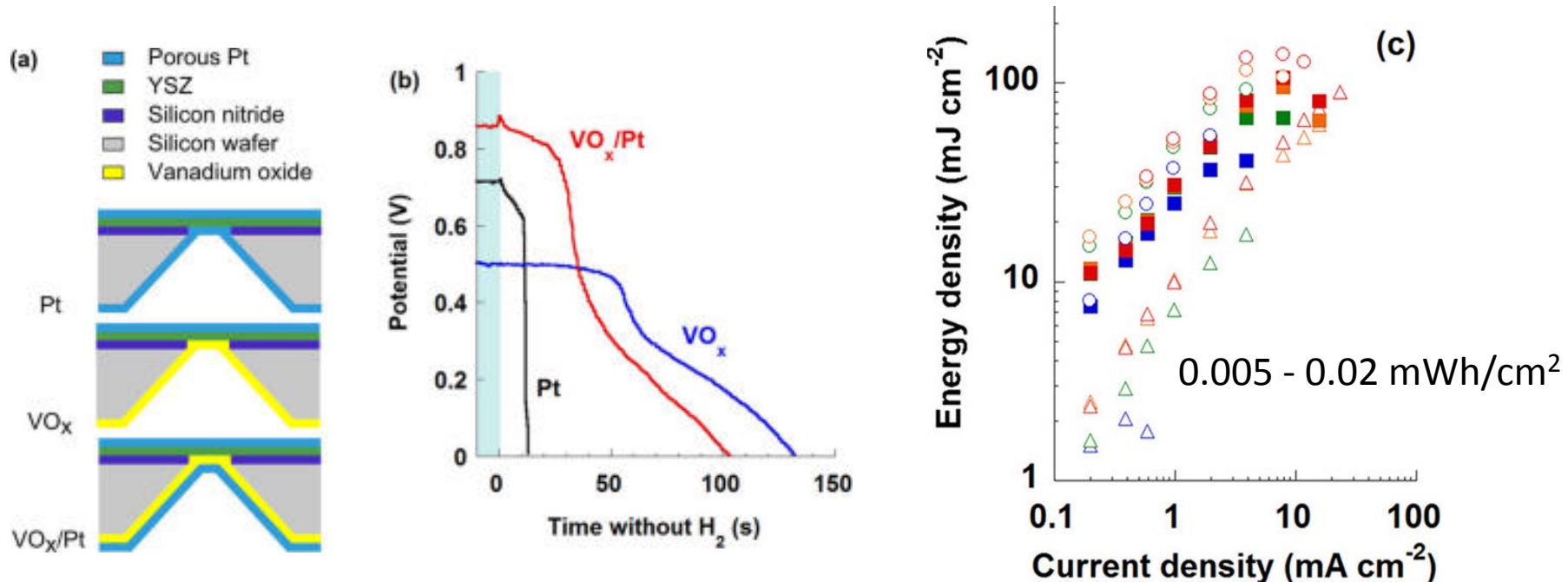
***In-situ* charge storage in anode**

Possible mechanisms for *in-situ* charge storage



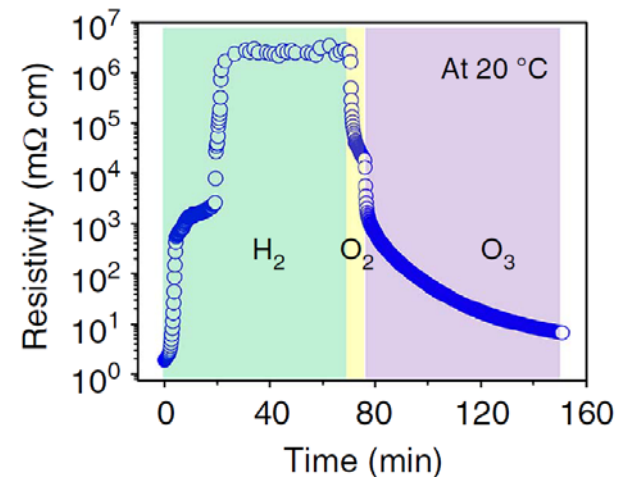
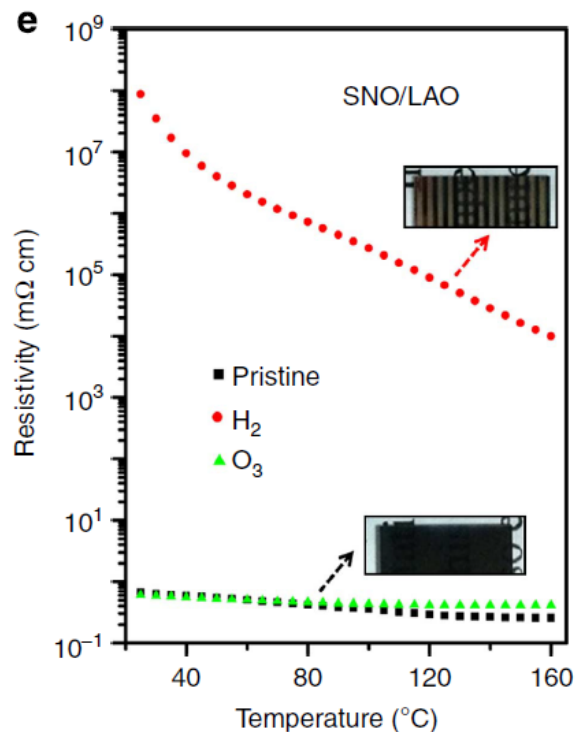
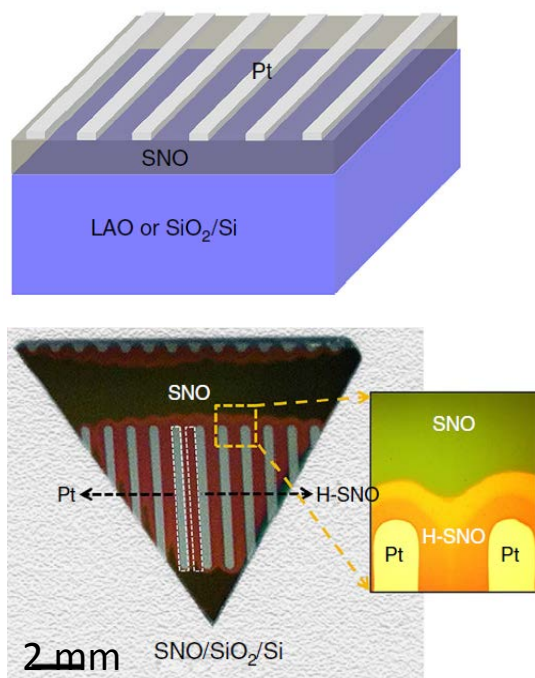
- So far, *in-situ* storage was observed in a few transition metal oxides.
- The most likely mechanisms for the *in-situ* storage are the following.
 - Cation valence oxidation (such as VO_2/V_2O_5)
 - Hydrogen storage (Hydrides with H/V ratio 0.3-1.2 were reported)

Battery-like response in VO₂ film



- Testing was performed at 300 °C using ultra-thin film YSZ platform.
- V⁴⁺ to V⁵⁺ transition observed in vanadia film after battery mode operation.
- Energy density was 20-100 mJ/cm² (0.005-0.02 Wh/cm²) tested at 0.1-10 mA/cm².

Hydrogen intercalation in SmNiO_3 thin film



Resistivity and optical properties of perovskite oxide (nickelate) can be tuned by several orders of magnitude by doping hydrogen.



**Direct hydrocarbon operation at
300-500°C with carbide catalyst**

Transition metal carbide catalyst for direct hydrocarbon oxidation at 300-500°C

Catalyst development is necessary to operate SOFCs with hydrocarbon fuels at 300-500 °C

- Steam reforming is not favorable below 650 °C.
- Coking is a major challenge with Nickel catalyst.

Transition Metal Carbide Catalyst

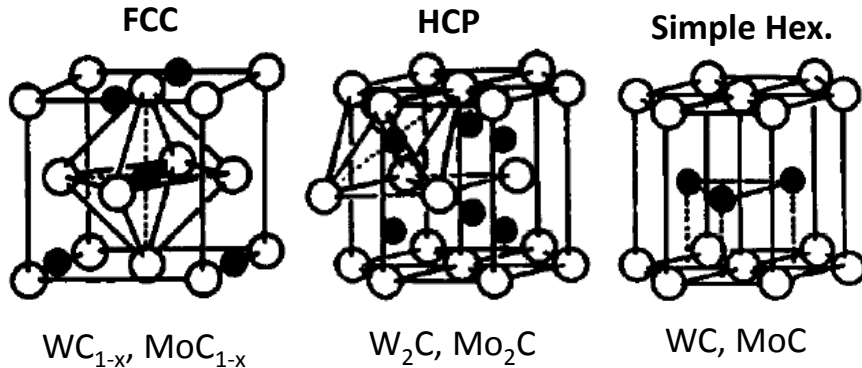
- Catalytic properties similar to Pt-group metals. ^[1]
- High electronic conductivity comparable to metals.
- Resistant to coarsening due to very high melting point (e.g., WC: 2870 °C).
- Resistant to coking demonstrated in direct methane SOFC. ^[2]

[1] S. T. Oyama, *The Chemistry of Transition Metal Carbides and Nitrides*, Chapman & Hall (1996).

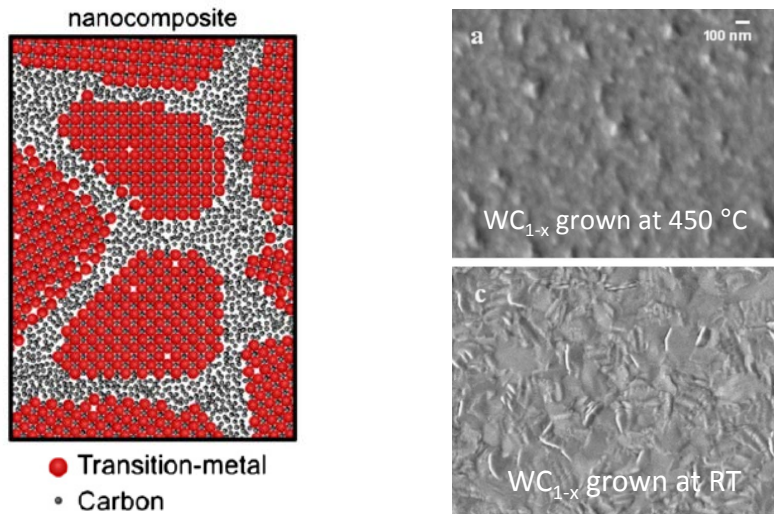
[2] Torabi and Etsel, *J. Electrochem. Soc.*, 159(6), B714 (2012).

Structure of carbides (bulk and thin film)

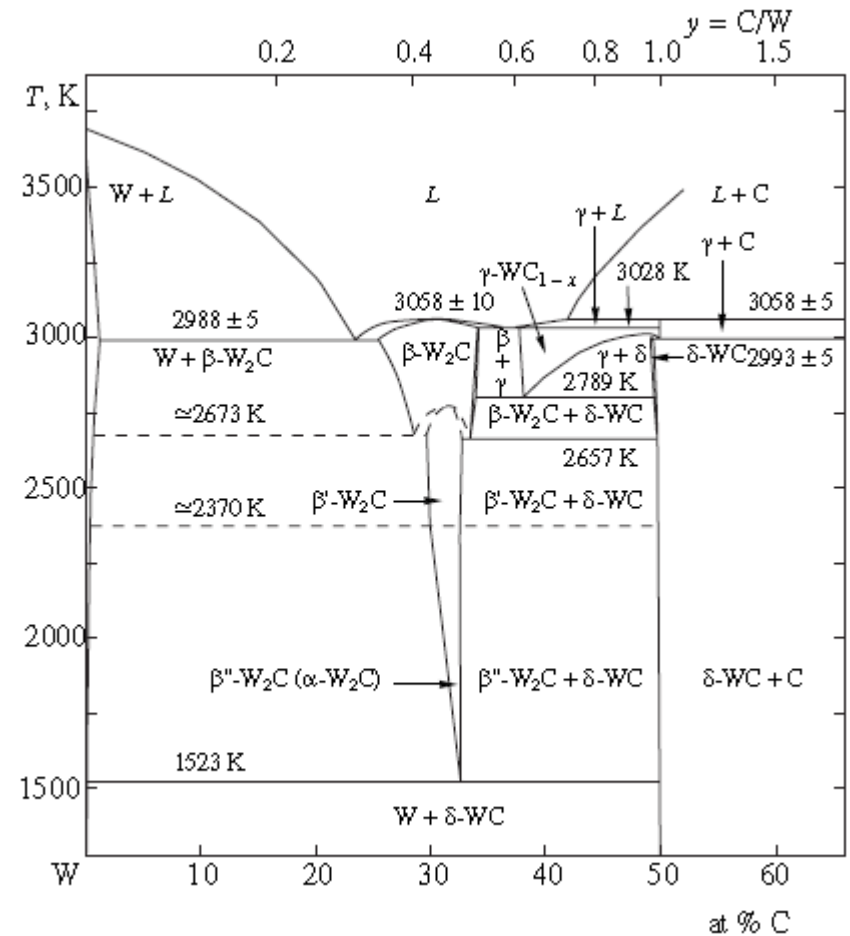
Crystal structure of carbide [1]



Structure of sputtered WC [2,3]



W-C Phase Diagram [4]



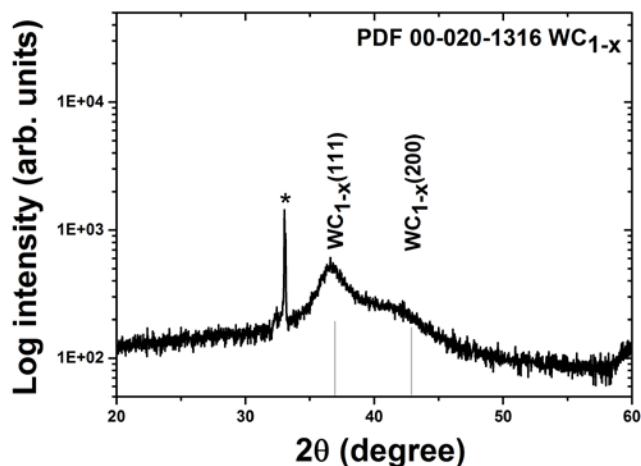
[1] S. T. Oyama, *Catalysis Today*, **15**, 179-200 (1992).

[2] Jansson *et al.*, *Thin Solid Films*, **536**, 1 (2013).

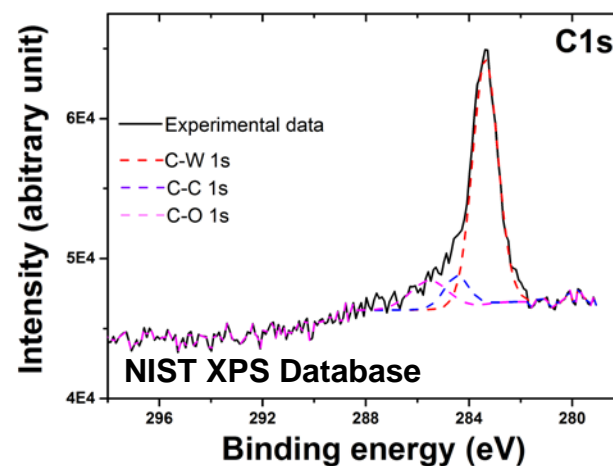
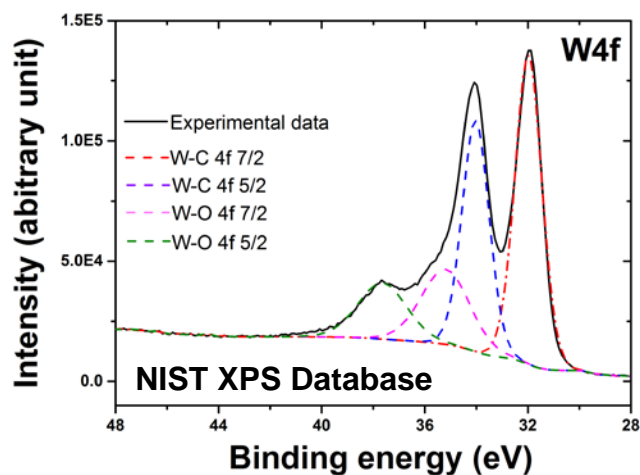
[3] Weigert *et al.*, *J. Vac. Sci. Tech A*, **26**, 23 (2008).

[4] Kurlov and Gusev, *Inorg Mater*, **42**(2), 121 (2006).

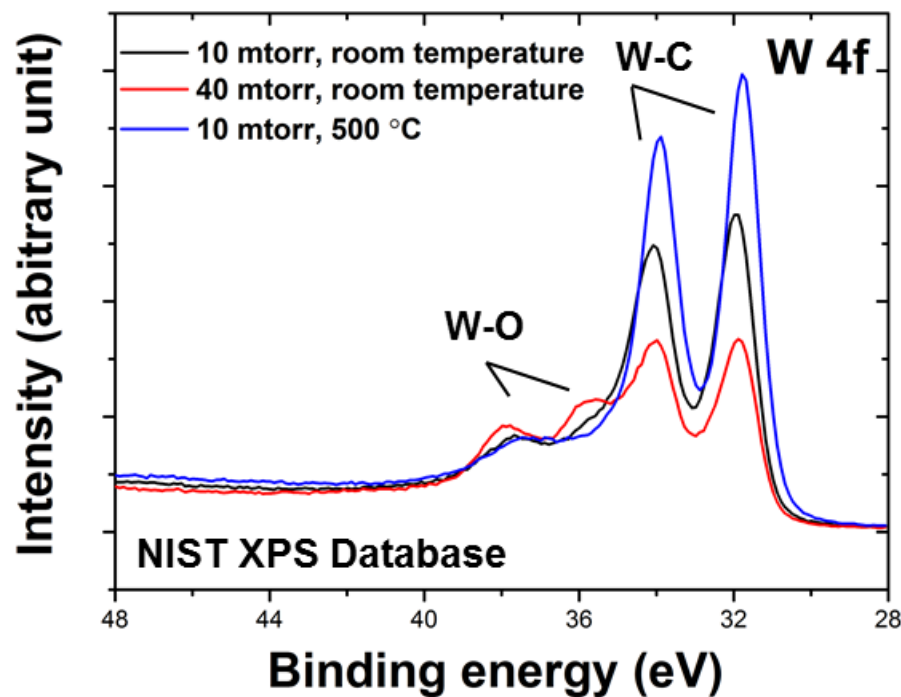
Thin film WC is nonstoichiometric (WC_{1-x})



- WC thin films prepared at 150 W, 10 mtorr and room temperature were found to be mainly (111) oriented WC_{1-x} (PDF 00-020-1316);
- W4f and C 1s confirm WC's existence;



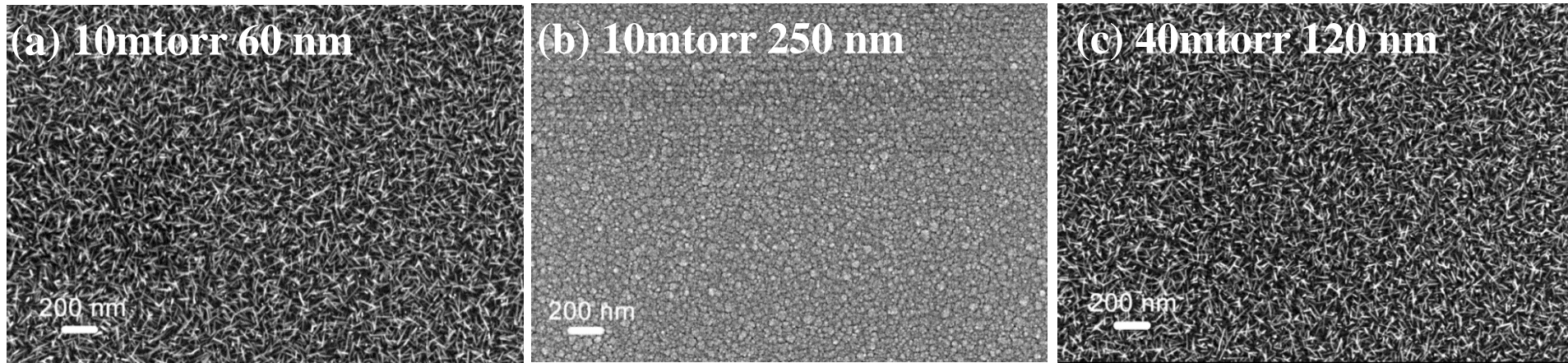
Composition of WC is very sensitive to the growth conditions



- W-C intensity increases with deposition temperature, while decrease with deposition pressure;
- W-O intensity increase with deposition pressure;

Challenges in using carbide in CH₄

WC was annealed in pure CH₄ under 500 °C for 4 h



- Unlike noble metal or oxide anodes, oxidation is a key challenge to use of WC as anode;
- The possible oxide products include WO₂, WO₃, and W₁₈O₄₉ ;
- Doping, and control of defects and interfaces can mitigate these issues.

Summary

- Nanoscale thin film electrolyte is an excellent platform to lower the operating temperature of solid oxide fuel cells down to 300-500 °C.
- *In-situ* charge storage in anode was demonstrated by integrating transition metal oxide in anode.
- Transition metal carbide catalyst has been investigated as a catalyst to activate C-H bond at below 650 °C.

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- **SiEnergy Team**

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